

Version with Markings to Show Changes Made

*Amendments*

*In The Claims*

Please cancel claims 31, 37, 47, 66 and 71-80 without any disclaimer or a prejudice to and amend claims 29, 32, 36, 64 and 71, as follows.

29. (Three times Amended) A method for manufacturing a thin film transistor array panel for a liquid crystal display, comprising the steps of:

forming a gate wire including a gate line and a gate electrode connected to the gate line on an insulating substrate;

forming a gate insulating layer covering the gate wire;

forming a semiconductor pattern on the gate insulating layer;

forming a data wire including a source electrode, a drain electrode and a data line connected to the source electrode on the semiconductor pattern, wherein the gate insulating layer, the semiconductor pattern and the data wire are patterned in a single photolithography step;

forming a passivation layer covering a color filter before forming red, green and blue color filters;

forming color filters made of photosensitive material, the color filters covering data wire and having a first contact hole; and

forming a pixel electrode connected to the drain electrode through the first contact hole of the color filters.

32. (Amended) The method of claim 29[31], wherein the passivation layer is made of photosensitive transparent organic material having a good planarization property.

46. (Twice Amended) A thin film transistor array panel for a liquid crystal display, comprising:

a gate wire including a gate line and a gate electrode connected to the gate line, and formed on an insulating substrate;

a gate insulating layer covering the gate electrode;

a semiconductor pattern formed on the gate insulating layer;

a data wire including a source electrode and a drain electrode, and a data line connected to the source electrode;

a passivation layer covering the data wire and having a first contact hole exposing the drain electrode; [and]

red, green, and blue color filters formed under the passivation layer; and

a pixel electrode connected to the drain electrode through the first contact hole.

wherein the gate wire or the data wire are made of photodefinable conductive material.

48. (Amended) The thin film transistor array panel of claim 46[47], wherein the passivation layer and the color filters are made of photosensitive material.

64. (Twice mended) A thin film transistor array panel for a liquid crystal display, comprising:

- a plurality of gate lines formed on an insulating substrate;
- a gate insulating layer covering the gate lines;
- a plurality of data lines intersecting the gate lines;
- an amorphous silicon layer formed under the entire data lines;
- an ohmic contact layer interposed between the data lines and the amorphous silicon layer;
- an array of thin film transistors, each transistor including a gate electrode connected to the gate line, a source electrode connected to the data line, and a drain electrode;
- a plurality of color filters formed over the gate insulating layer, the color filters overlapping the data lines at least in part; and
- a plurality of pixel electrodes formed on the color filters, each pixel electrode electrically connected to the drain electrode.